Materials List for:

Synthesis and Characterization of High c-axis ZnO Thin Film by Plasma Enhanced Chemical Vapor Deposition System and its UV Photodetector Application

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Materials

| Name | Company | Catalog Number | Comments |
|----------------------------|----------------------------------|----------------|-----------------------------------|
| RF power supply | ADVANCED ENERGY | RFX-600 | |
| Butterfly valve | MKS | 253B-1-40-1 | |
| Mass flow controller | PROTEC INSTRUMENTS | PC-540 | |
| Pressure controller | MKS | 600 series | |
| Heater | UPGRADE INSTRUMENT CO. | UI-TC 3001 | |
| Sputter gun | AJA INTERNATIONAL | A320-HA | |
| DEZn 1.5M | ACROS ORGANIC USA, New Jersey | | also called Diethylzinc (C2H5)2Zn |
| Spin coater | SWIENCO | PW - 490 | |
| I-V measurement | Keithley | Model: 2400 | |
| Photocondutive measurement | Home-built | | |
| UV light sourse | Panasonic | ANUJ 6160 | |
| Mask aligner | Karl Suss | MJB4 | |
| Photoresist | Shipley a Rohm & Haas company | S1813 | |
| Developer | Shipley a Rohm & Haas company | MF319 | |
| Silicon wafer | E-Light Technology Inc | 12/0801 | |
| Glass substrate | CORNING | 1737 | P-type / Boron |